



# A Reliable Low-area Low-power PUF-based Key Generator

Dr. Raimondo Luzzi, Infineon Technologies AG

ECW, November 18-21, 2024, Rennes

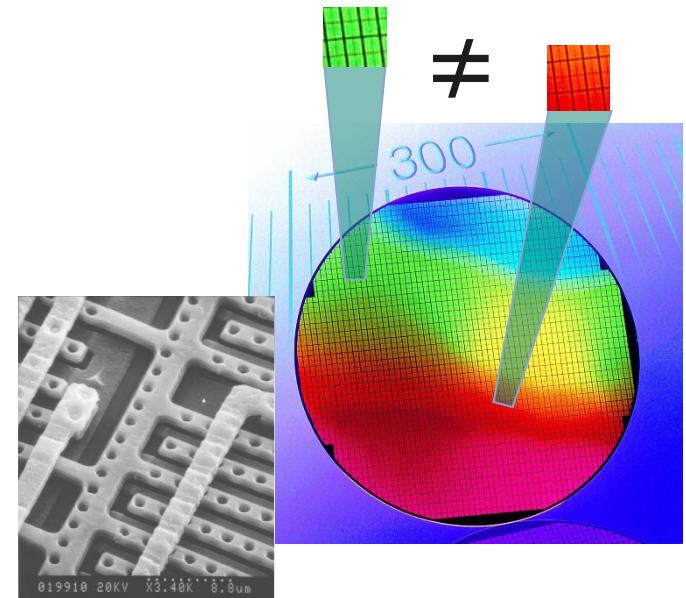


# Agenda

- Two-Stage ID (TSID) PUF cell vs. standard latch
- Pre-selection technique
- 128-bit key generator implementation
- Experimental results in 65nm
- Conclusions

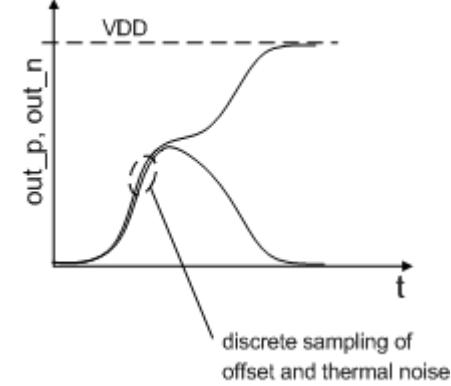
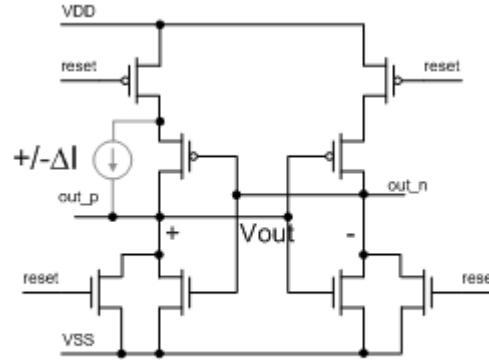
# Physically unclonable functions as “fingerprints” of objects

- extracting small variations which make each micro electronic device unique
- variations beyond manufacturer's control
- generating an ID code on the fly
- secure against probing (at least before digitalization...)
- in high sec applications: additional security feature, not replacing NVM stored keys

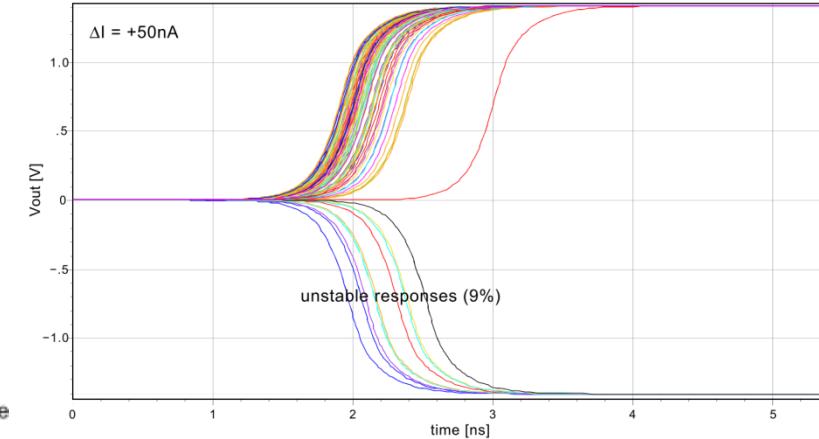


# Latch vs. Two-stage ID (TSID) cell

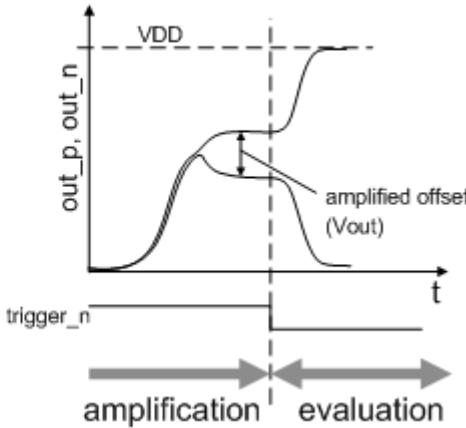
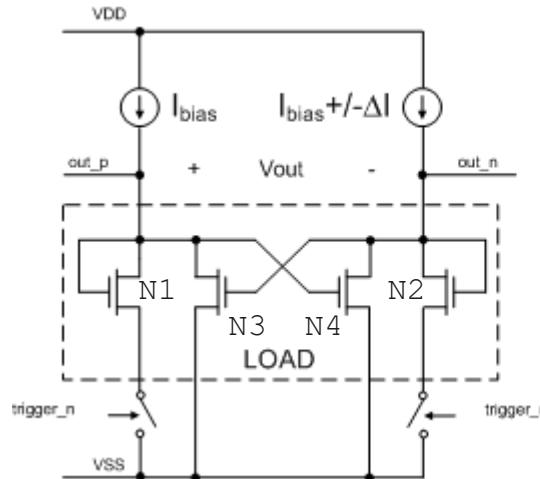
## ■ Latch



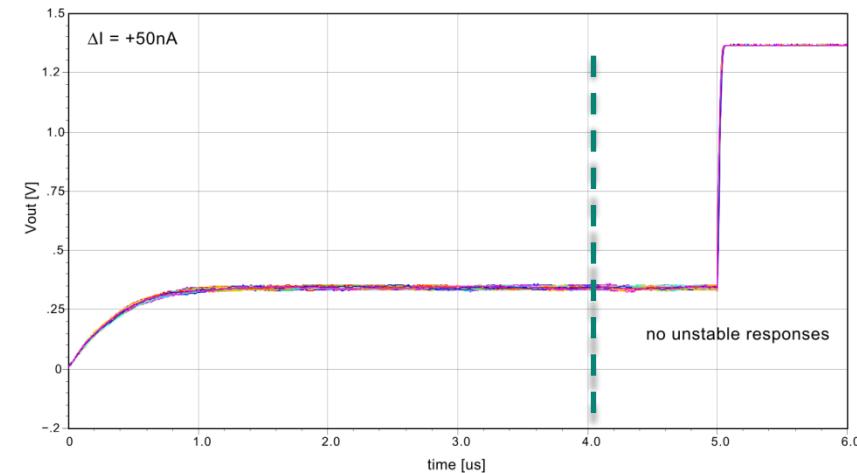
transient noise simulation (100 runs)



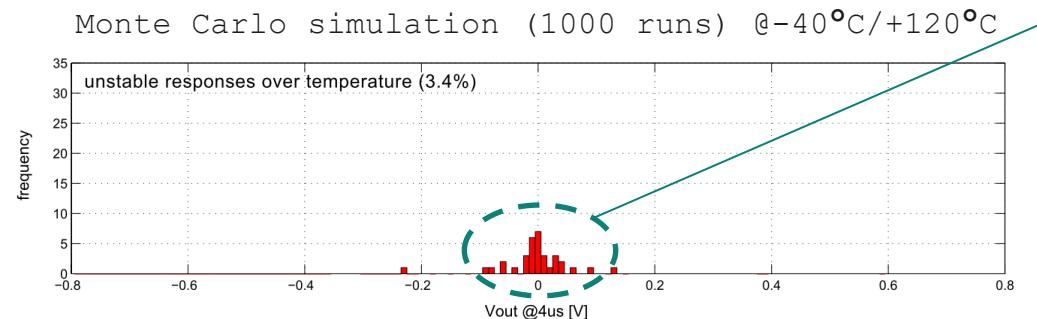
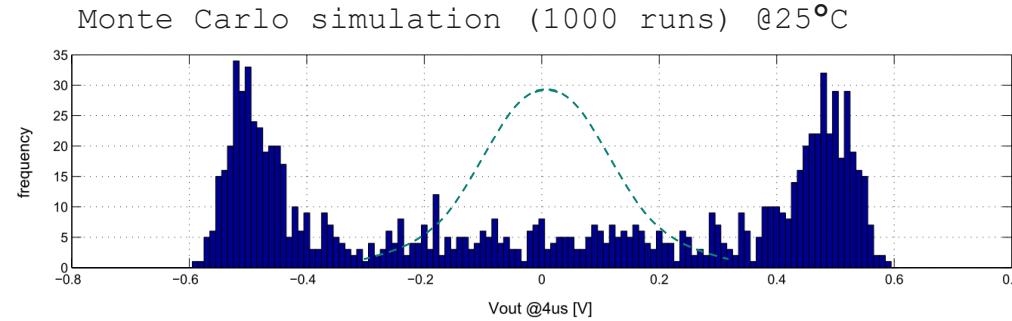
## ■ Two-Stage ID cell



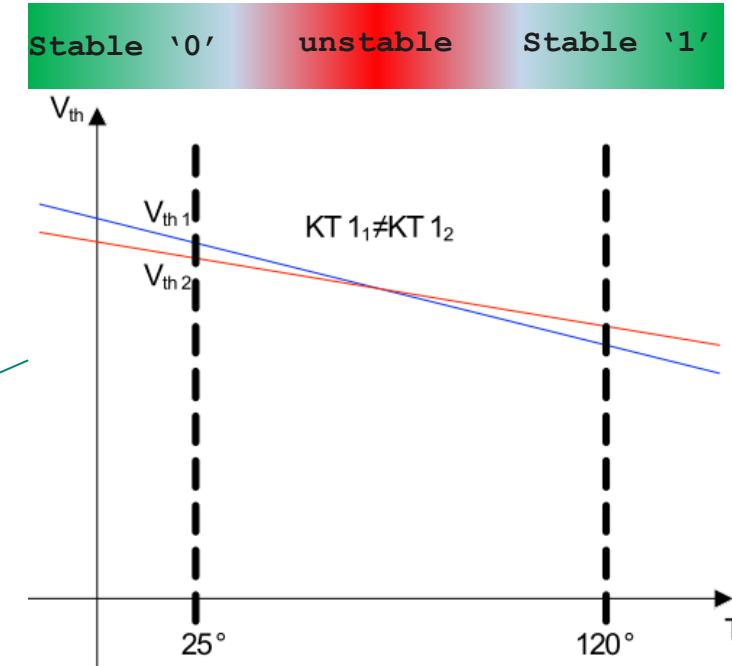
transient noise simulation (100 runs)



# Temperature instability



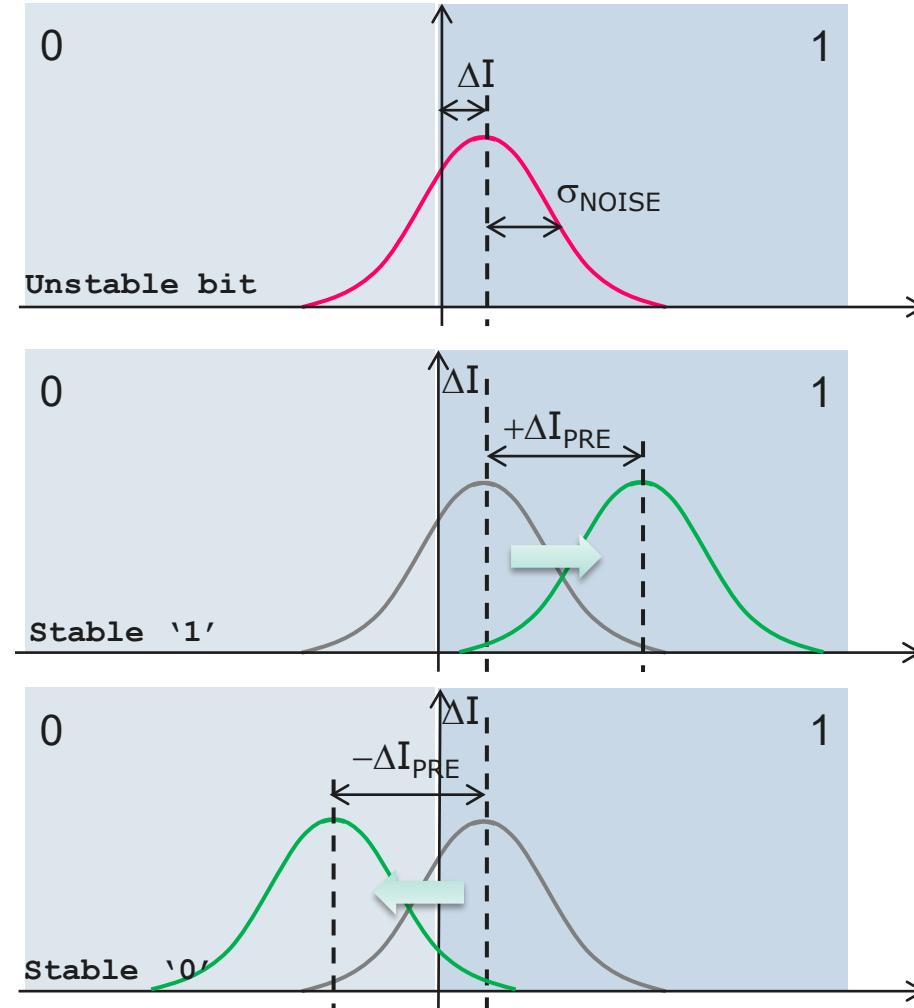
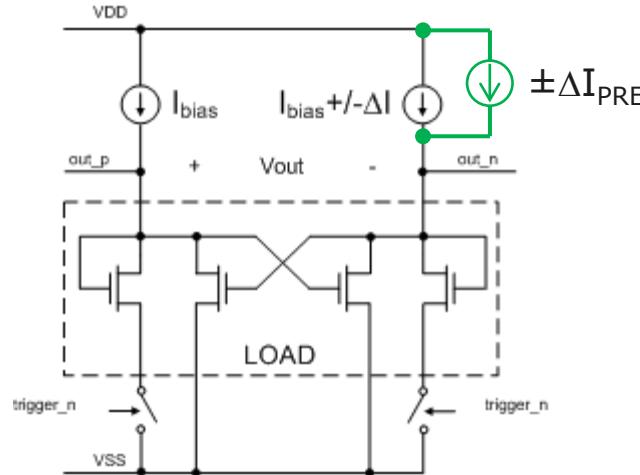
Distribution of unstable cells:  $V_{out} @ -40^\circ\text{C} \neq V_{out} @ 120^\circ\text{C}$



- Due to the mismatch of the  $V_{th}$  temperature coefficient  $KT_1$ , the output may change its value → ca. **3.4%** unstable bits in simulation

# Pre-selection [Hofer et al. CHES 2010]

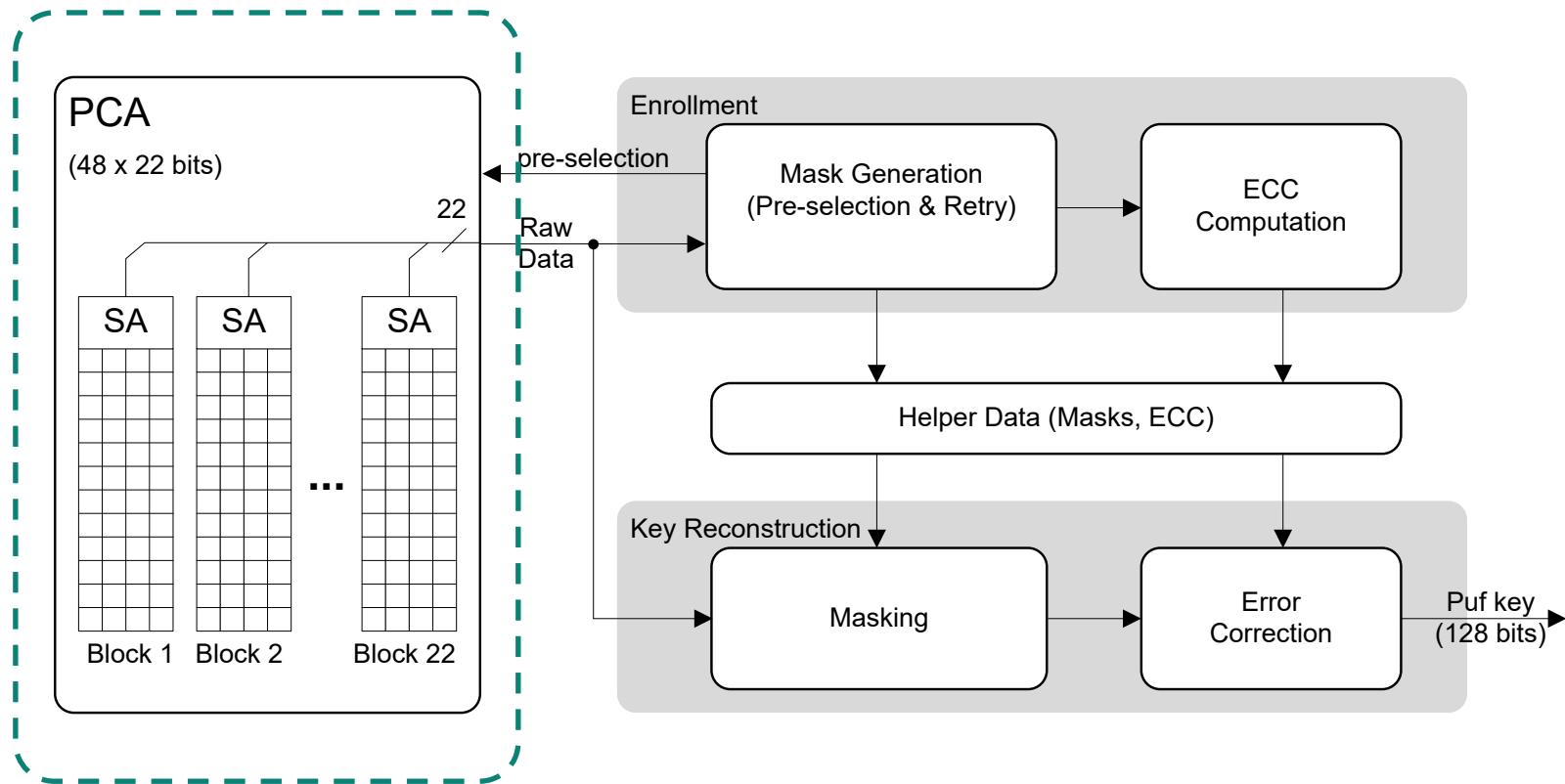
- Idea: select those cells that provide a reasonable degree of mismatch



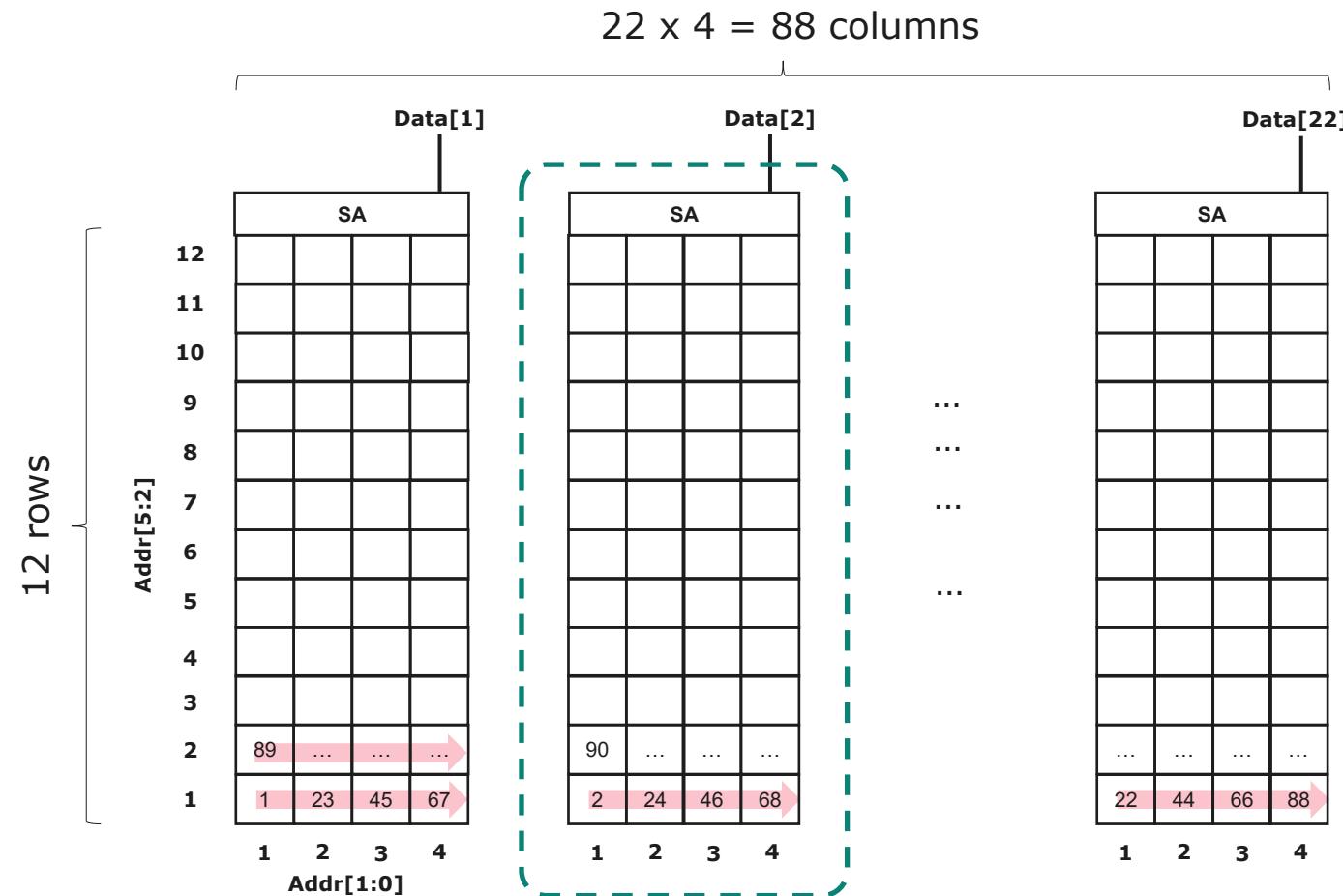
- If  $\text{out}@+\Delta I_{\text{PRE}} \neq \text{out}@-\Delta I_{\text{PRE}}$ , the cell is marked as unstable and sort out

M. Hofer, C. Böhm, "An Alternative to Error Correction for SRAM-Like PUFs", Proc. CHES 2010, LNCS 6225, pp. 335-350, 2010

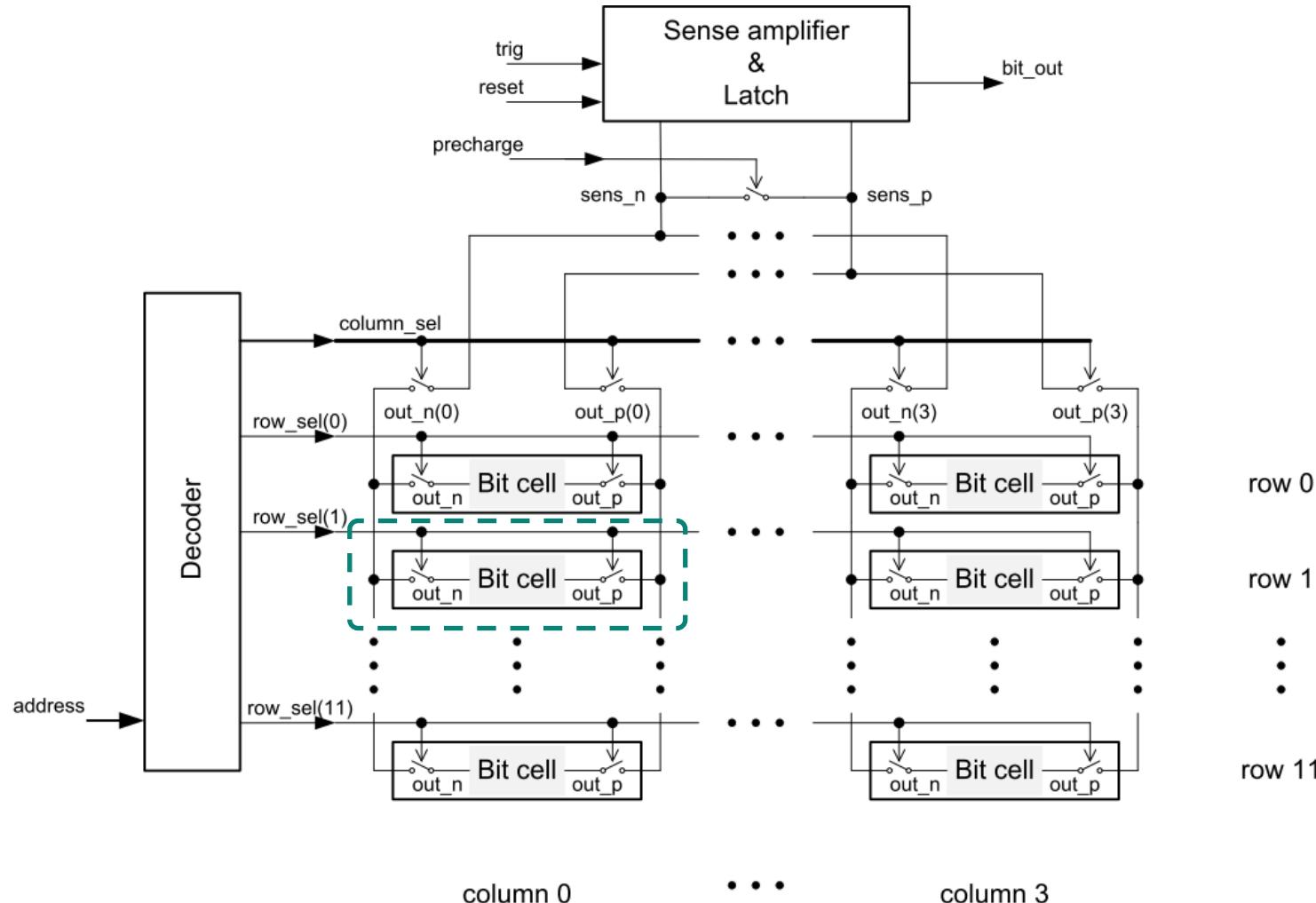
# TSID PUF Key Generator



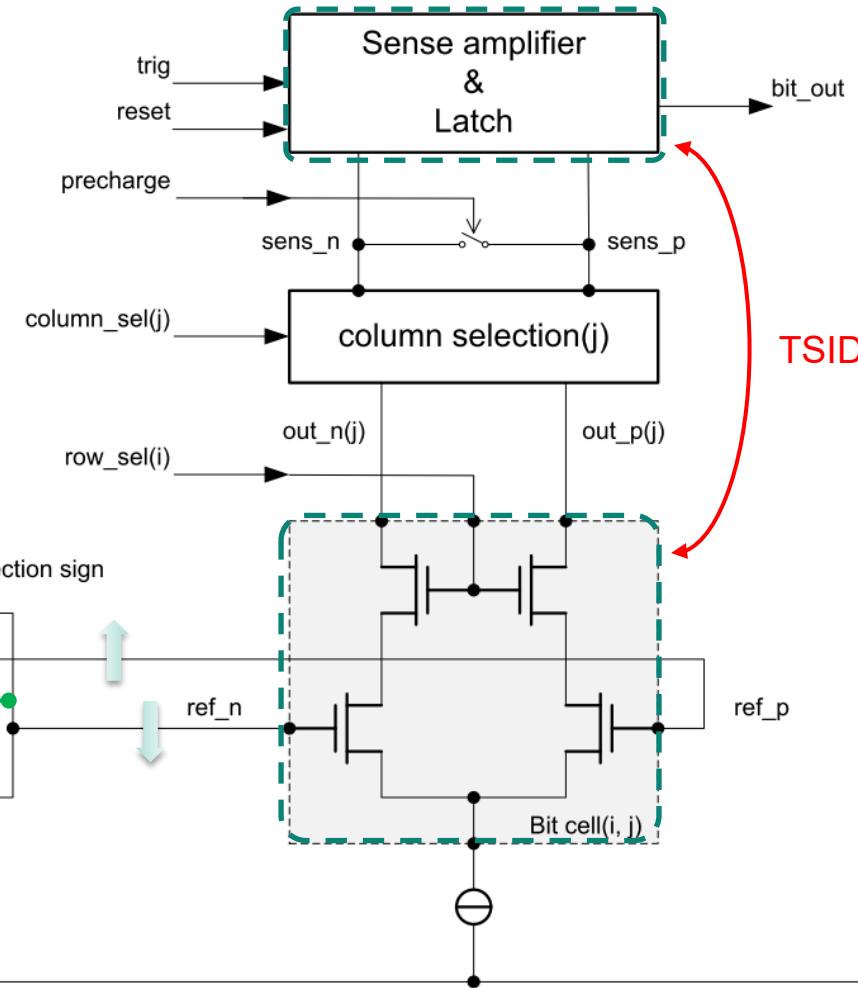
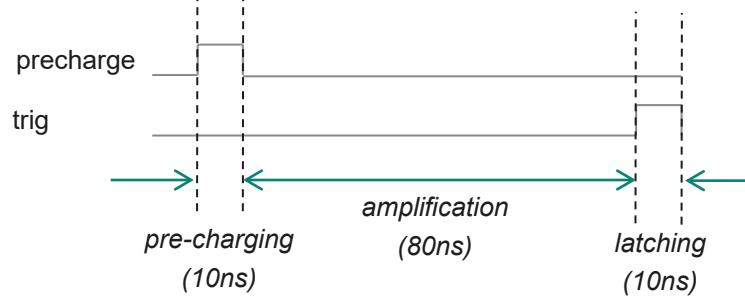
# PUF Cell Array (PCA)



# Block implementation



# Cell implementation (with pre-selection)

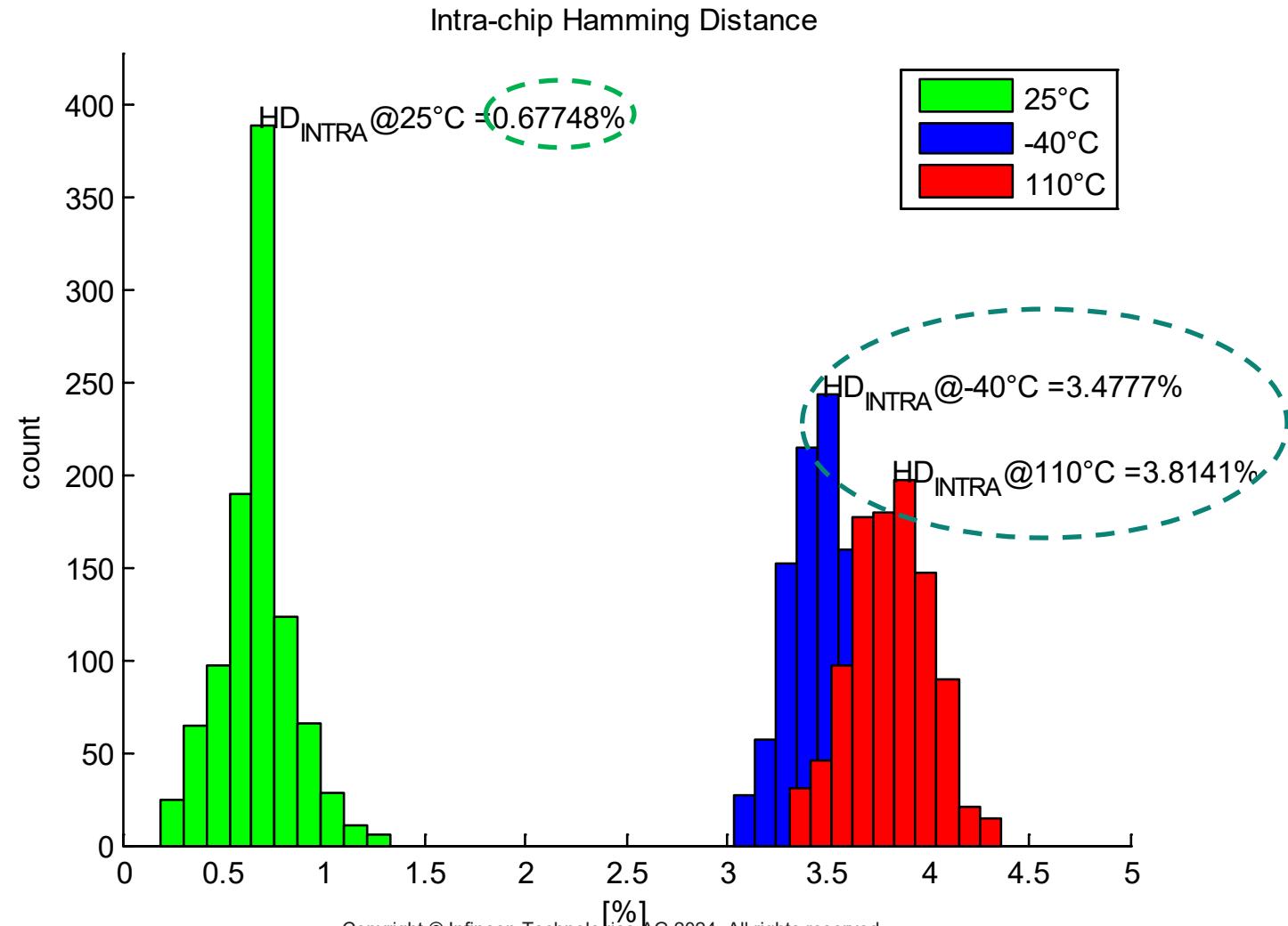


# Experimental results

- Intra-chip Hamming distance
- Pre-selection test
- Stability
- Inter-chip Hamming distance
- Correlation between two neighboring bits

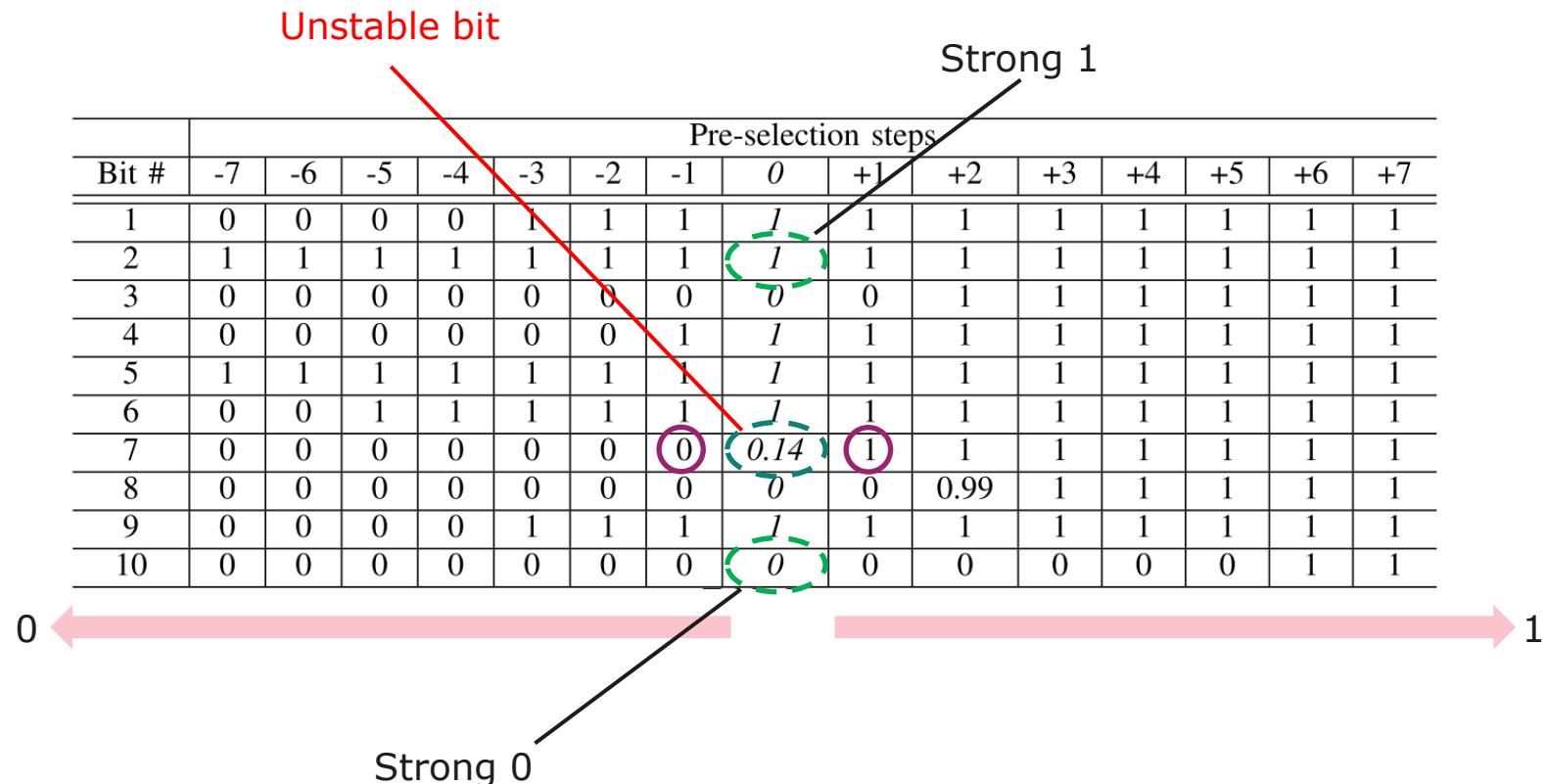
# Intra-chip Hamming Distance

- NOM module, **1000 readouts**
- Reference run generated @25°C
- **no pre-selection**



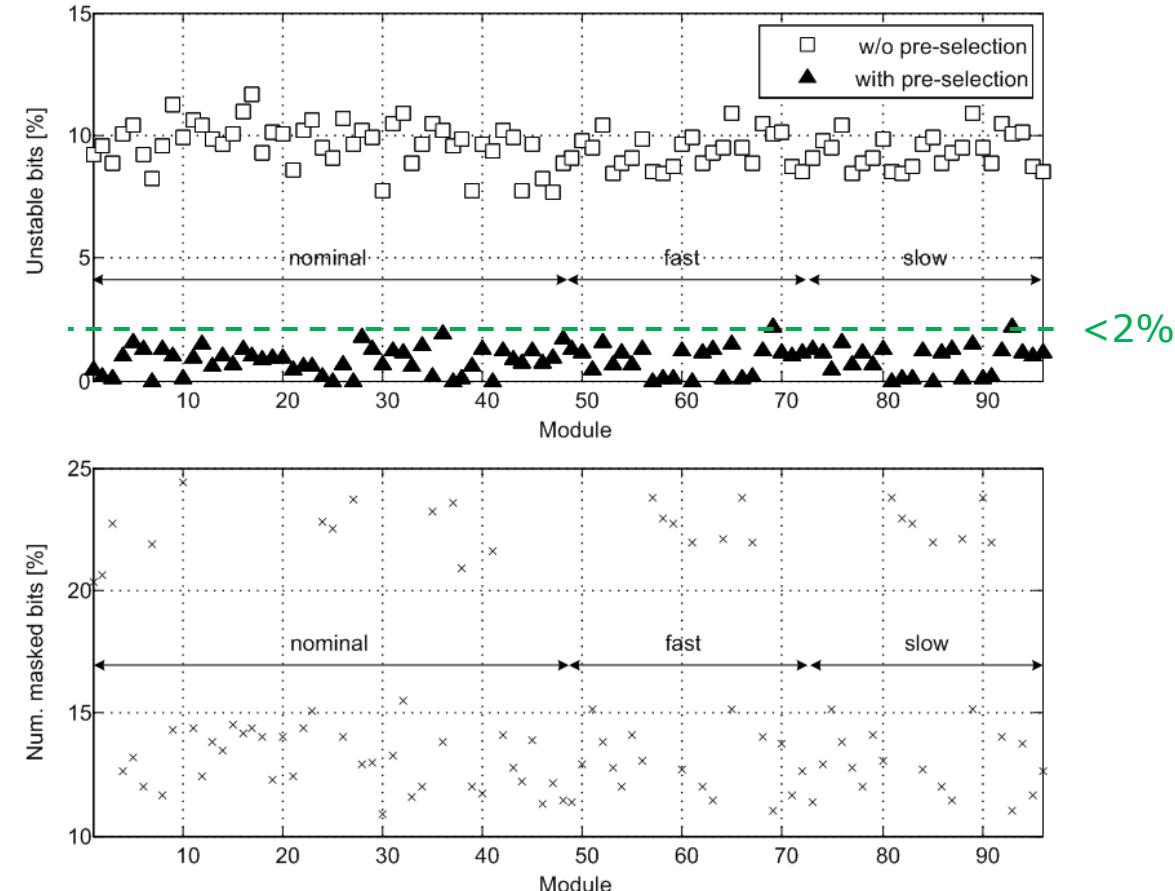
# Basic pre-selection test

- NOM module, **100 readouts**
- Reference run generated @25°C



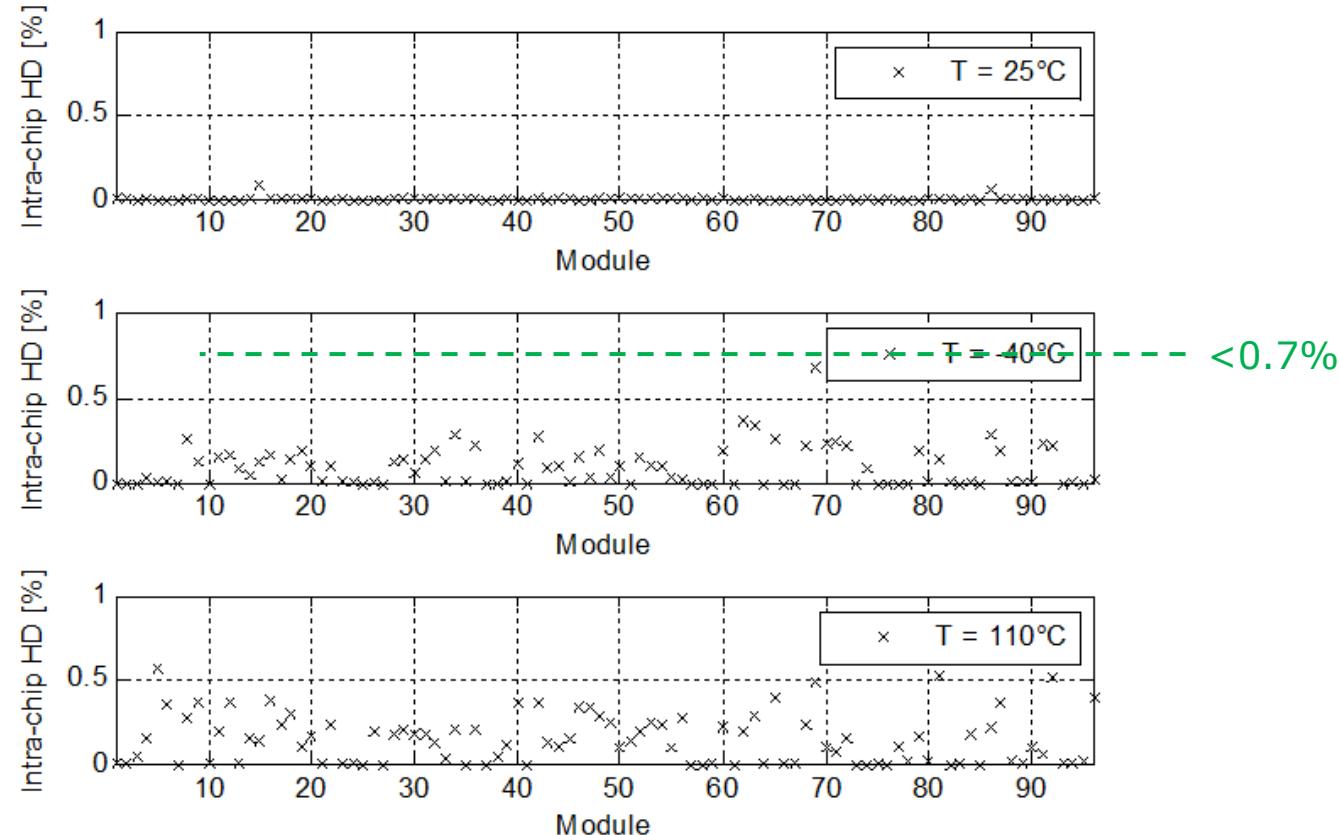
# Stability

- 96 modules (NOM/FAST/SLOW), **1000 readouts**
- Reference run generated @25°C
- Tested temperatures: -40°C/+25°C/+110°C
- **with and w/o pre-selection**
- readout of the PUF repeated **16 times** (for both pre-selection directions)



# Intra-chip Hamming Distance

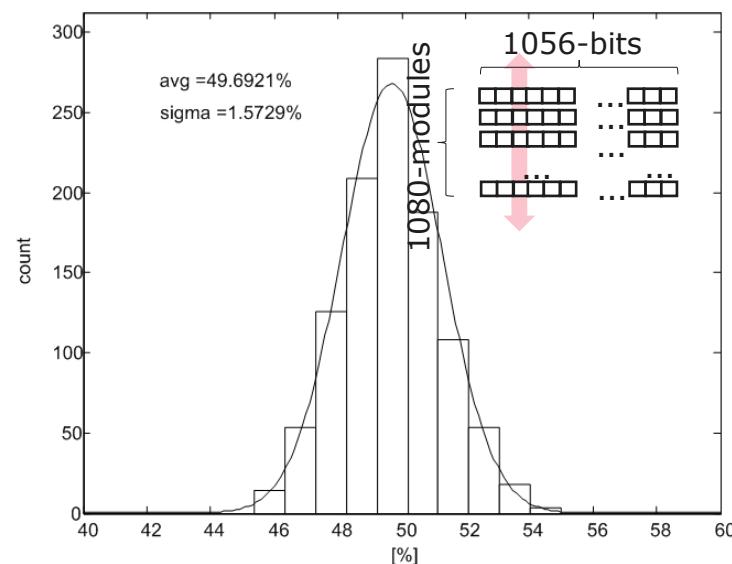
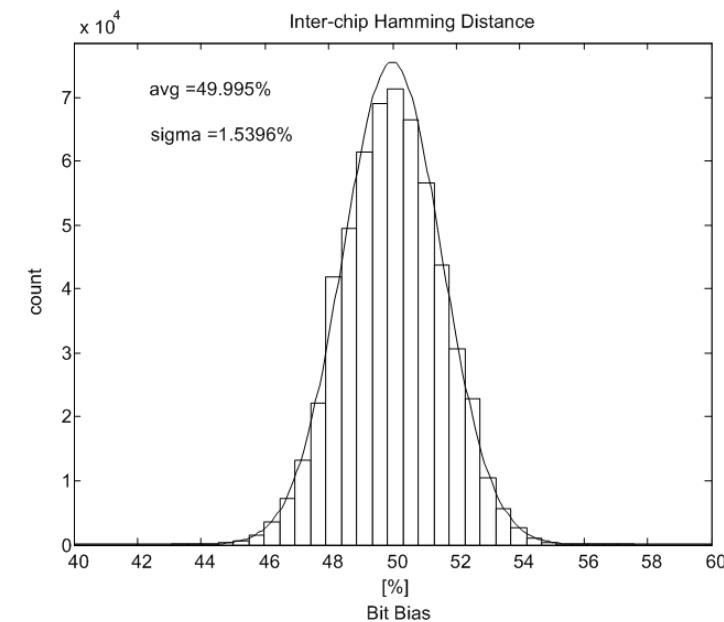
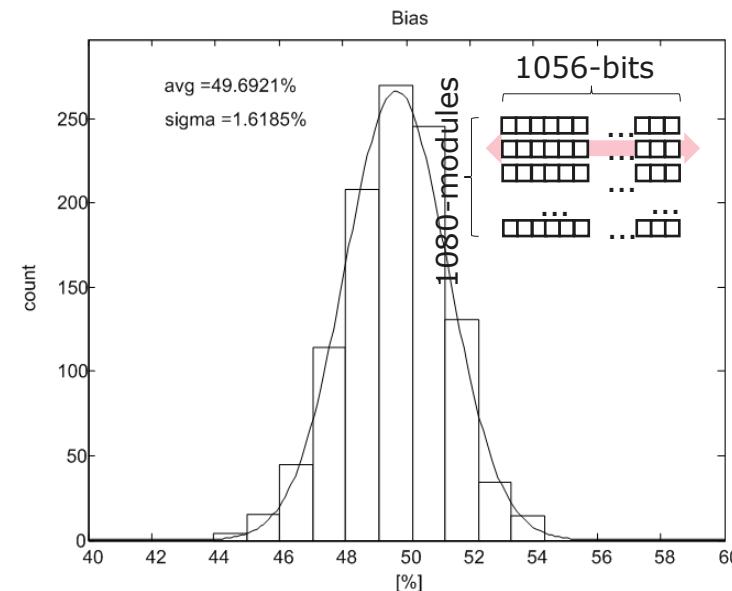
- 96 modules (NOM/FAST/SLOW), **1000 readouts**
- Reference run generated @ $25^{\circ}\text{C}$
- Tested temperatures:  $-40^{\circ}\text{C}/+25^{\circ}\text{C}/+110^{\circ}\text{C}$
- **with pre-selection**
- readout of the PUF repeated **16 times** (for both pre-selection directions)



- Worst case intra-chip HD @ $-40^{\circ}\text{C}$ : 0.7%

# Inter-chip Hamming Distance & Bias

- **1080** modules (NOM/SLOW/FAST x360)
- Inter-chip HD = 49.995%
- Bias = 49.6921%
- Bit bias = 49.6921%



## Correlation between neighboring bits

- Horizontal correlation:

$$R_H(j, i) = \left| \frac{1}{N} \sum_{k=1}^N (PCA_k(i, j) \oplus PCA_k(i, j + 1)) - 0.5 \right|$$

- Vertical correlation:

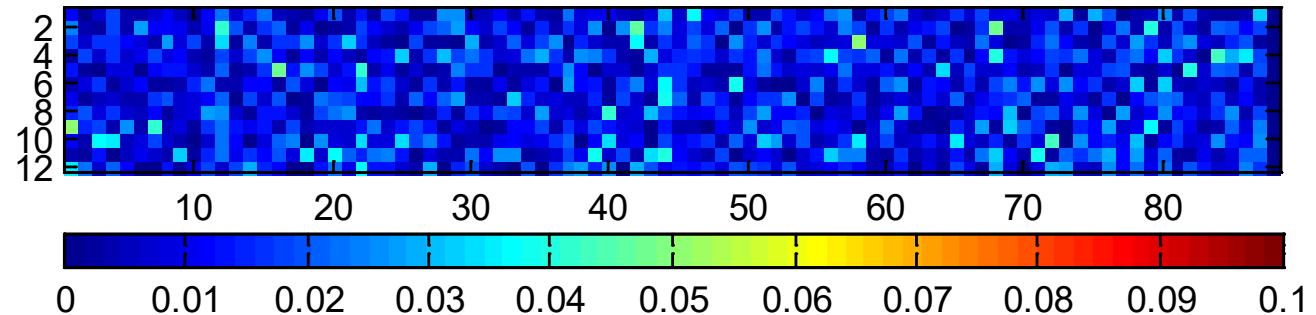
$$R_V(j, i) = \left| \frac{1}{N} \sum_{k=1}^N (PCA_k(i, j) \oplus PCA_k(i + 1, j)) - 0.5 \right|$$

- where: N is the number of tested modules and  $PCA_k(i, j)$  is the bit in position  $(i, j)$  of the k-th module

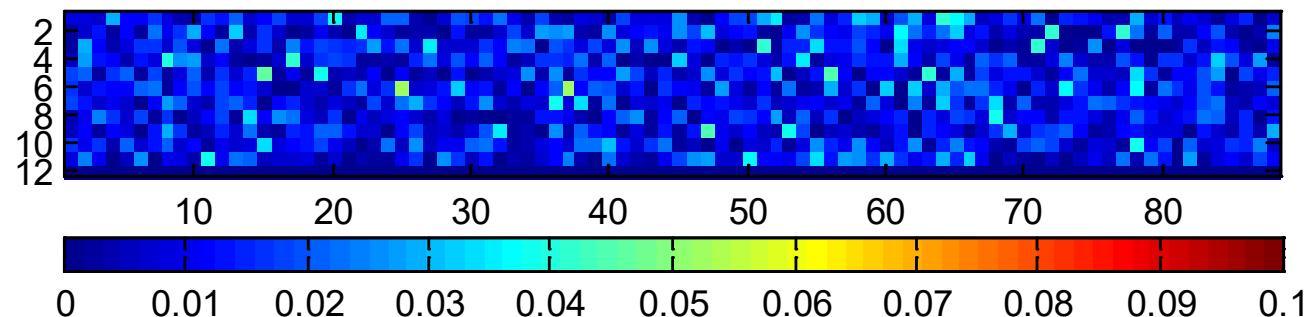
# Correlation between neighboring bits

■ 1080 modules (10x36 NOM, 10x36 FAST, 10x36 SLOW)

horizontal correlation



vertical correlation



## Conclusions

- A 128-bit PUF-based key generator using the TSID cell and the pre-selection technique
- Low area:
  - Total PCA area: 3250um<sup>2</sup>, bit cell area: 2.4um<sup>2</sup> (< 4 times smaller than a SRAM cell)
- Low power:
  - Energy consumption per bit: 42fJ/bit.
- Reliability:
  - Intra-chip HD < 0.7% (under all conditions)
  - After 10<sup>6</sup> key reconstruction @-40°C and + 110°C, on 2000 devices from different wafers  
(in total **5 x 10<sup>9</sup>** key generations), no single fail has been detected!

# Thank you!

